

## PATENT ABSTRACTS OF JAPAN

(11)Publication number : 2001-181868

(43)Date of publication of application : 03.07.2001

(51)Int. Cl.

C23F 1/18

(21)Application number : 11-361152

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(22)Date of filing : 20.12.1999

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(54) MICROETCHING AGENT FOR COPPER AND COPPER ALLOY

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a microetching agent capable of executing microetching free from the generation of unevenness in etching even in the case microstains such as oily components are present on the surface of copper.

SOLUTION: This microetching agent for copper and/or copper alloys is composed of an aqueous solution containing (a) ferric sulfate (III), (b) sulfuric acid and (c) nonionic surfactant, the concentration of (a) is 1 to 40 wt.%, the ratio of (b) to 100 pts.wt. of (a) is 5 to 50 pts.wt., the concentration of (c) is 0.01 to 10 wt.%, the content of halogen is 0.01 to 20 wt.%, and suitably, (d) phosphoric acid of 0.01 to 30 wt.%, or (e) carboxylic acid of 0.01 to 30 wt.%, or (d) phosphoric acid of 0.01 to 15 wt.% and (e) carboxylic acid of 0.01 to 15 wt.% are contained.

## LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

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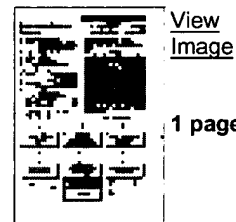
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IKEDA KIMIHIKO;  
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[News, Profiles, Stocks and More about this company](#)**Published / Filed: 2001-07-03 / 1999-12-20****Application Number: JP1999000361152****IPC Code: C23F 1/18;****Priority Number: 1999-12-20 JP1999000361152****Abstract:**

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1 page